

BEST AVAILABLE REPRODUCTION

What is claimed is:

1. A chuck equipment comprising  
a plate-shaped base,  
a first electrode to which a first voltage is applied,

5 and

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a second electrode to which a second voltage  
different from the first voltage in magnitude is applied,  
the first and second electrodes being insulated from each  
other and arranged on a surface of said base.

10 2. The chuck equipment according to claim 1, wherein  
said surfaces of said first and second electrodes are  
exposed.

15 3. The chuck equipment according to claim 2, wherein  
the chuck equipment is constructed in such a manner that a  
substrate is placed on the surface of said chuck equipment  
on which said first and second electrodes are arranged to  
cause said substrate to be brought into contact with said  
first and second electrodes.

20 4. The chuck equipment according to claim 2, wherein  
the surface of said base is flush with the surfaces of said  
first and second electrodes.

5. The chuck equipment according to claim 2, wherein  
an insulating convexity portion is arranged between said  
first and second electrodes.

25 6. The chuck equipment according to claim 2, wherein

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said first and second electrodes have a protective film on the surfaces thereof and said protective film is exposed.

7. The chuck equipment according to claim 6, wherein the chuck equipment is constructed in such a manner that a substrate is placed on the surface of said chuck equipment on which said first and second electrodes are arranged to cause said substrate to be brought into contact with said protective film formed on said first and second electrodes.

8. The chuck equipment according to claim 2, wherein said first electrode is spaced apart from said second electrode by 2mm or less.

9. The chuck equipment according to claim 2, wherein said first and second electrodes are 4mm or less in width.

10. The chuck equipment according to claim 2, comprising a plurality of said first and second electrodes arranged thereon, wherein region where said first and second electrodes are alternately arranged is provided.

11. The chuck equipment according to claim 2, comprising a third electrode to which a third voltage different from said first and second voltages is applied.

12. A vacuum processing apparatus comprising a vacuum chamber in which the chuck equipment according to claim 2 is arranged.

13. The vacuum processing apparatus according to claim 12, comprising a power supply for establishing an

*14. The vacuum processing apparatus according to claim 13, wherein a protective plate is arranged around said chuck equipment, and the vacuum processing apparatus is constructed in such a manner that a substrate is placed on said chuck equipment to cause said substrate to be accommodated in said protective plate.*

*sub  
1A'*

electric field of  $1.0 \times 10^6$  V/m or greater between said first and second electrodes.